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Docket No. TRANSMITTAL OF INFORMATION DISCLOSURE STATEMENT 8381/ETCH/SILICON/JB Under 37 CFR 1.97(b), (c), or (d) In re Application of: Davis, et al. Examiner Group Art Unit Serial No. Filing Date 10/805,136 03/19/2004 METHOD FOR CONTROLLING A PROCESS FOR FABRICATING INTEGRATED DEVICES Title: Address to: **Commissioner for Patents** Alexandria, VA 22313-1450 DEC 2 3 2004 37 CFR 1.97(b) The information Disclosure Statement submitted herewith is being filed within three months of the filing of a national 1. application other than a continued prosecution application under 37 CFR 1.53(d); within three months of the date of entry of the national stage as set forth in 37 CFR 1.491 in an international application; before the mailing of a first Office Action on the merits; or before the mailing of a first Office Action after the filing of a request for continued examination under 37 CFR 1.114. 37 CFR 1.97(c) The Information Disclosure Statement submitted herewith is being filed after the period specified in 37 CFR 1.97(b), but 2. □ prior to the mailing date of a Final Action under 37 CFR 1.113, a Notice of Allowance under 37 CFR 1.311, or an Action that otherwise closes prosecution in the application, and is accompanied by the statement or fee as indicated below. 37 CFR 1.97(d) The Information Disclosure Statement submitted herewith is being filed after the period specified in 37 CFR 1.97(c), but 3. on or before payment of the issue fee and is accompanied by the statement and fee as indicated below. Required Statements and/or Fees Under 37 CFR 1.97(c) or (d) Each item of information contained in the accompanying Information Disclosure Statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of the Information Disclosure Statement. (37 CFR 1.97(e)(1)) No item of information in the accompanying Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application, and, to the knowledge of the undersigned person, after making reasonable inquiry, no item of information contained in the accompanying Information Disclosure Statement was known to any individual designated in 37 CFR 1.56(c) more than three months prior to the filing of the Information Disclosure Statement. (37 CFR 1.97(e)(2)) The fee set forth in 37 CFR 1.17(p). Please credit any overpayment or charge any insufficiencies to deposit account number 20-0782. 37 CFR §1.704(d) Each item of information in the accompanying Information Disclosure Statement was cited in a communication from a П foreign patent office in a counterpart application and this communication was not received by any individual designated in 37 CFR-§1.56(c) more than thirty days prior to the filing of the Information Disclosure Statement. Dated: 12/17 Keith P. Taboada, Esq. Certificate of Mailing by First Class Mail I certify that this document is being deposited on 12-21-04 Reg. No. 45,150 with the U.S. Postal Service as first class mail under 37 CFR §1.8 Moser, Patterson & Sheridan, LLP and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 Attorneys at Law 595 Shrewsbury Avenue, Suite 100 Signature of Person Malling Correspondence Shrewsbury, New Jersey 07702 Barbara J. Jackson 732-530-9404 Typed or Printed Name of Person Mailing Correspondence

Sheet 1 of 1 sheet(s) Serial No. U.S. Department of Commerce, Patent and Trademark Office Docket No. 8381/ETCH/SILICON/JB1 10/805,136 (PTO Form 1449 modified) INFORMATION DISCLOSURE STATEMENT BY APPLICANT Confirmation Applicant No.: 8916 Davis, et al. Group (Use several sheets if necessary) Filing Date DEC 2 3 2004 March 19, 2004 Examiner **U.S. Patent Documents** TRADE NOW Filing Date If Applicant(s) Class Subclass Issue *Examiner Document Appropriate Name Number Date Initial 627 08/30/1988 156 Hieber Α1 4,767,496 250 492.2 A2 5,798,529 08/25/1998 Wagner 438 Toprac et al. 17 **A3** 5,926,690 07/20/1999 Α4 09/07/1999 Wang 156 345 5,948,203 430 30 12/21/1999 Ausschnitt et al. 6,004,706 A5 430 30 Ausschnitt et al. A6 6,027,842 02/22/2000 Rosenthal et al. 700 121 12/12/2000 A7 6,161,054 438 8 6,245,581 06/12/2001 Bonser et al. **8A** 356 388 A9 6,424,417 07/23/2002 Cohen et al. 257 48 A10 6,486,492 11/26/2002 Su 356 328 07/01/2002 2002/0171828 11/21/2002 Cohen et al. A11 **Foreign Patent Documents** Translation Country Class Subclass Date Document *Examiner Number Initial YES NO **B1** \Box B2 OTHER ART Including Author, Title, Date, Pertinent Pages, Etc. *Examiner Initial Lee, et al., "Analysis of Reflectometry and Ellipsometry Data from Patterned Structures," C1 Characterization and Metrology for UCSI Technology: 1998 International Conference, Seiler, et al., eds., pg 331-335 Raymond, "Angle-resolved scatterometry for semiconductor manufacture,", Microlithography C2 World, Winter 2000. Toprac, A., "AMD's Advanced Process Control of Ply-Gate Critical Dimension," Proc. SPIE Vol C3 3882, pg 62-65, Sept, 1999. Yang, et al., "Line-profile and Critical Dimension Measurements Using a Normal Incidence C4

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

Optical Metrology System," Proceedings of SPIE Vol. 4689, March 2002,

Date Considered

Examiner